

Maximum Multiplicity Distribution (MMD)

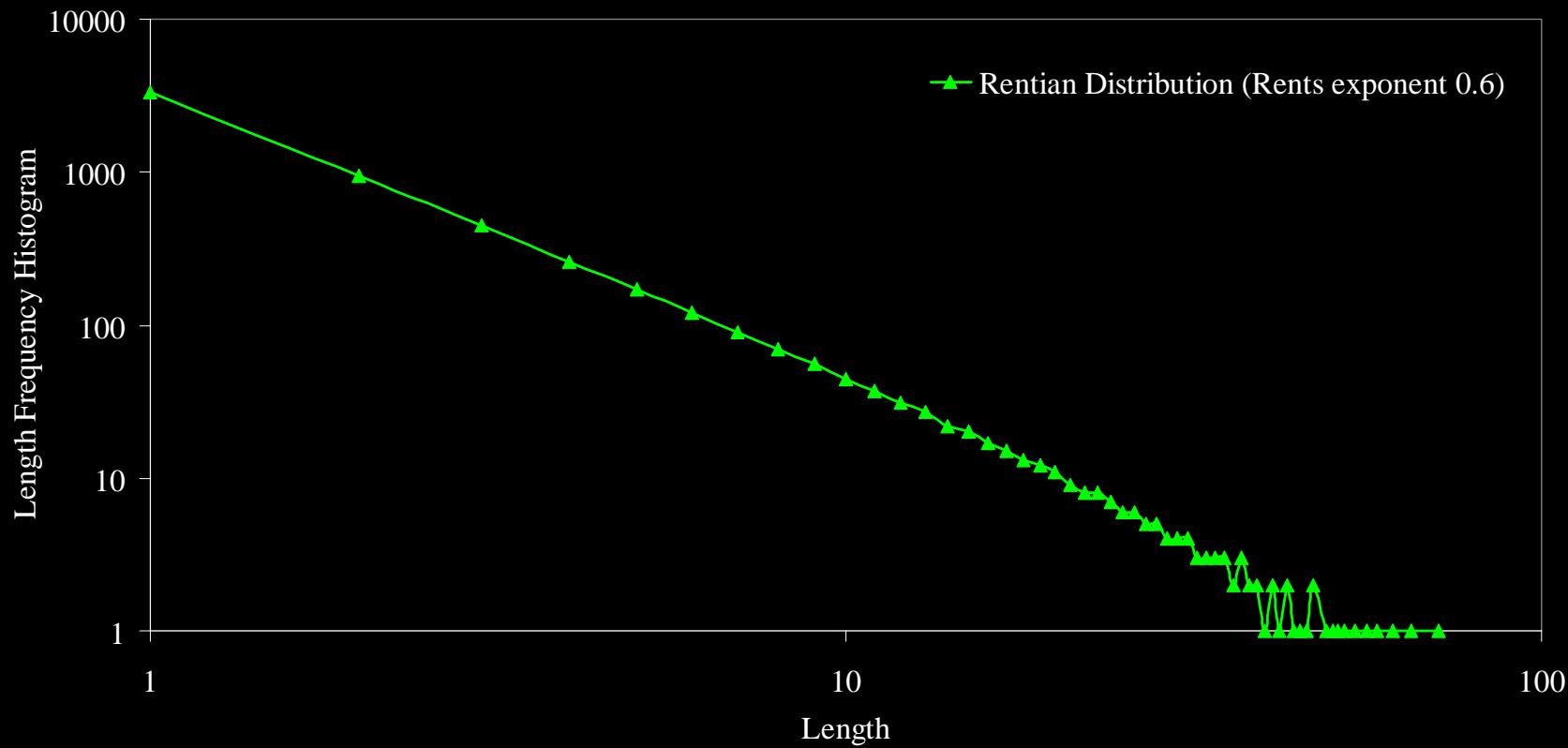
Pranav Anbalagan
Dr. Jeff Davis

Georgia Institute of Technology

*The authors gratefully acknowledge the support of the National Science Foundation (NSF# 0098227)
for this research.*

Rentian Length Distribution

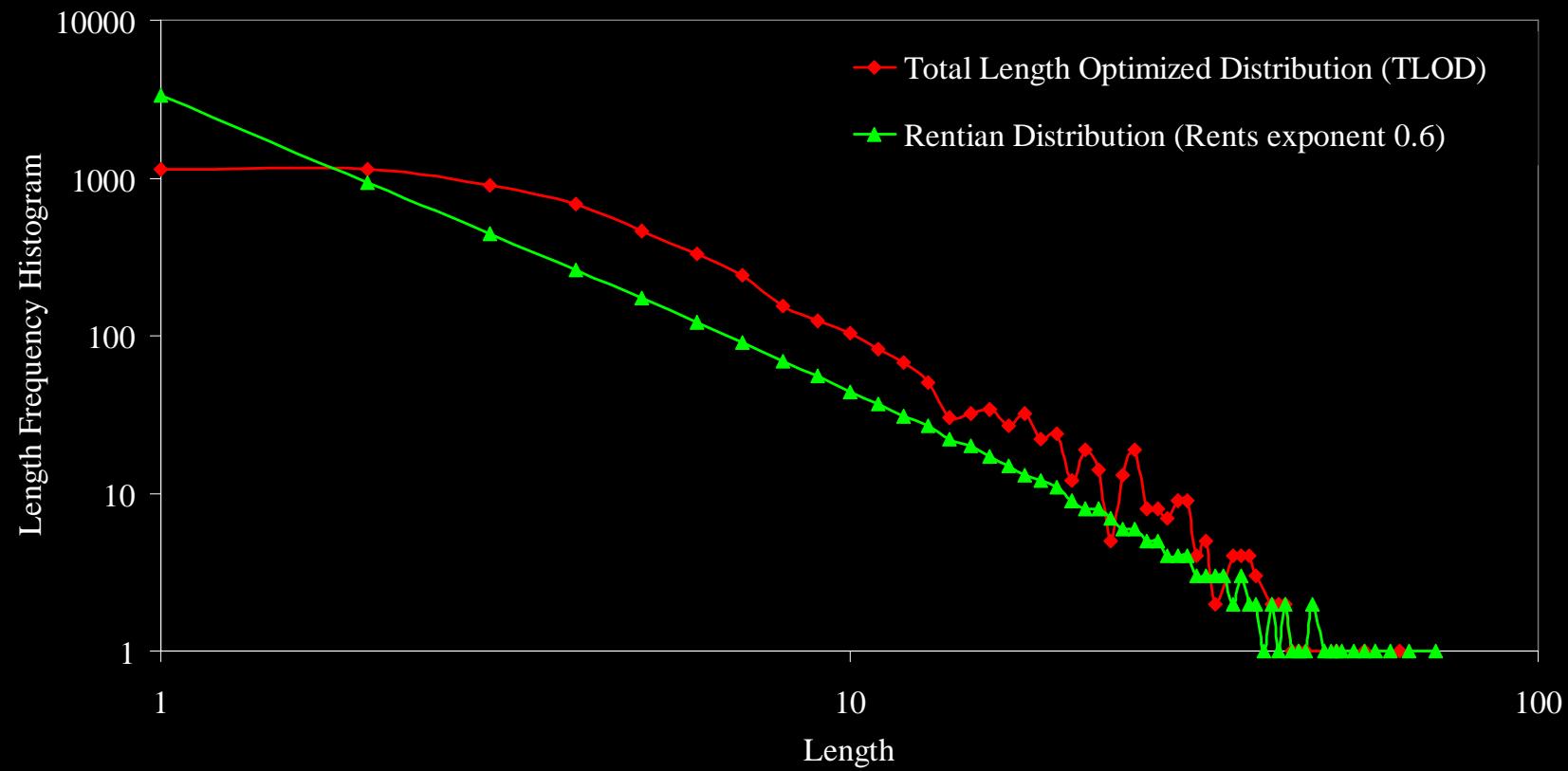
C7552 Benchmark Circuit: 3512 Gates; 5836 Interconnects



J. A. Davis, V. K. De, and J. D. Meindl, "A stochastic wire length distribution for gigascale integration (GSI) Part I: Derivation and Validation," IEEE Trans. Electron Devices, vol. 45, pp 580-589, March 1998.

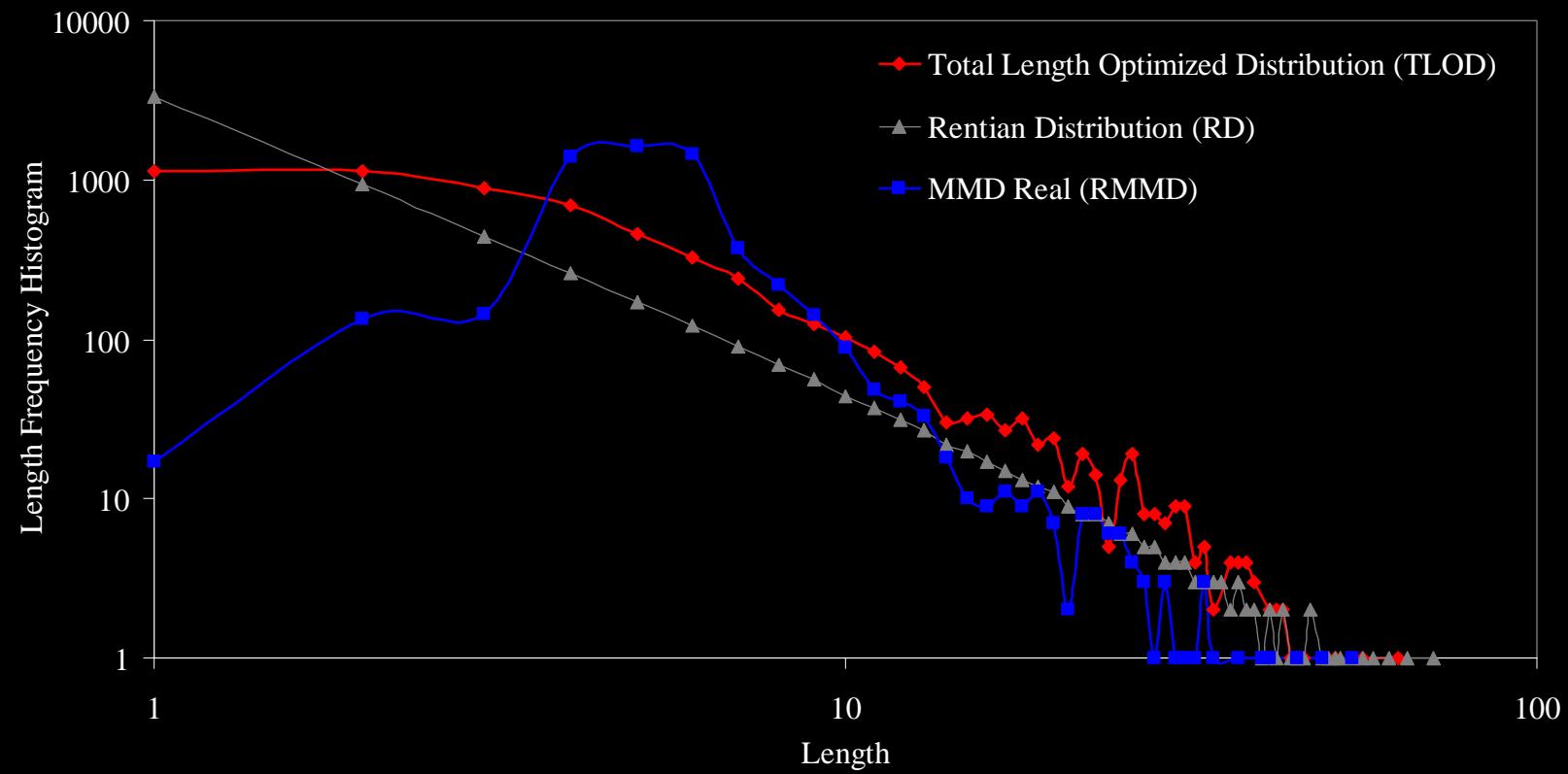
Length Distribution

C7552 Benchmark Circuit: 3512 Gates; 5836 Interconnects



Length Distribution

C7552 Benchmark Circuit: 3512 Gates; 5836 Interconnects



Salient Properties of New Distribution

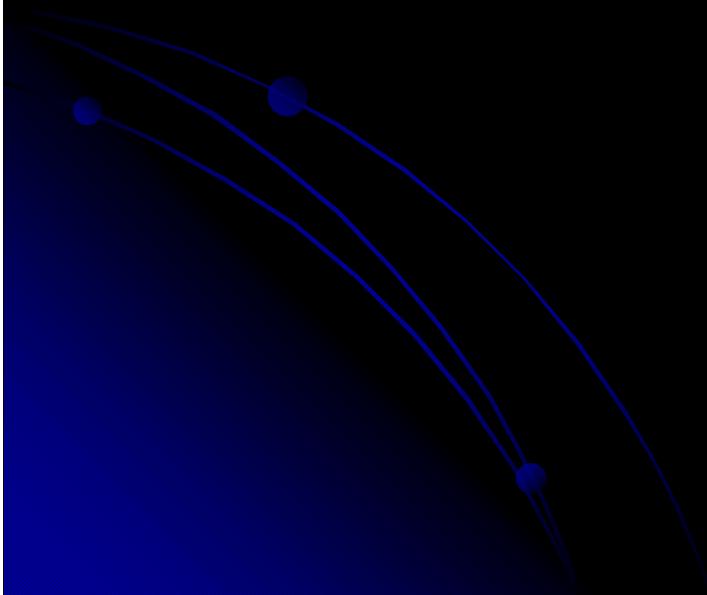
- Reduction in maximum length of interconnects
- Reduction in number of long interconnects
- Increases the available design space

Outline

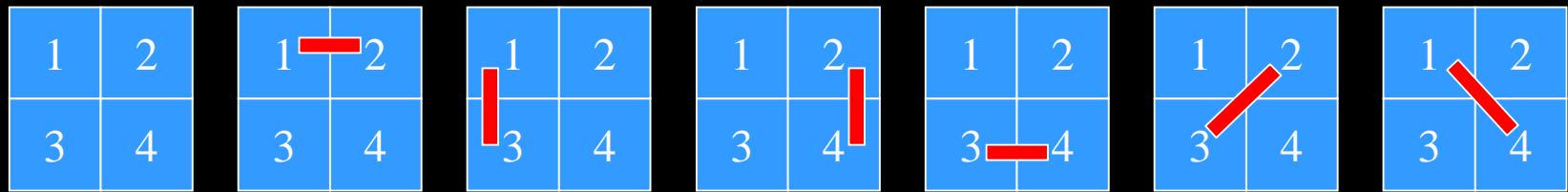
- *Multiplicity*
- Theoretical MMD
- Real MMD
- Impact on Global Interconnects
- Conclusion

Multiplicity of Length Distribution

*Total number of layout arrangements
that have the same length distribution*



Interconnect Positions

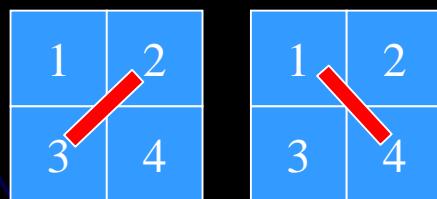


- $M[L]$: Number of interconnect positions of length L in a layout

- $M[1]=4$



- $M[2]=2$



Interconnect Positions

- Density of interconnect states function $M[L]$

$$1 \leq L < \sqrt{N} : \quad M[L] = \frac{L^3}{3} - 2L^2\sqrt{N} + \frac{1}{3}L(6N-1)$$

$$\sqrt{N} \leq L < 2\sqrt{N} - 2 : \quad M[L] = -\frac{L^3}{3} + 2L^2\sqrt{N} - \frac{1}{3}L(12N-1) + \frac{2}{3}\sqrt{N}(4N-1)$$

J. A. Davis, V. K. De, and J. D. Meindl, “A stochastic wire length distribution for gigascale integration (GSI) Part I: Derivation and Validation,” IEEE Trans. Electron Devices, vol. 45, pp 580-589, March 1998.

Multiplicity of Length Distribution

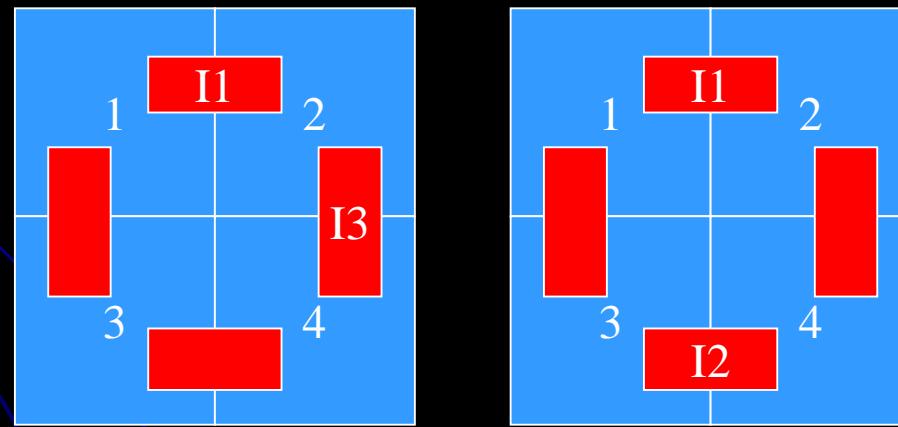
- Assumptions
 - Gates are arranged in a *homogeneous square layout array*
 - Interconnects are *independent*
 - Each interconnect is *distinct*

Independent Interconnects

- $N[1] = 2$



- Impossibilities Counted (Simple Calculations)!

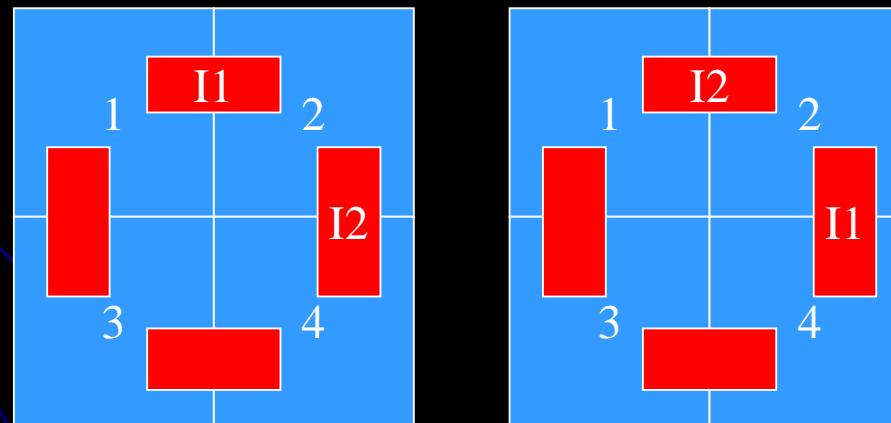


Distinct Interconnects

- $N[1] = 2$

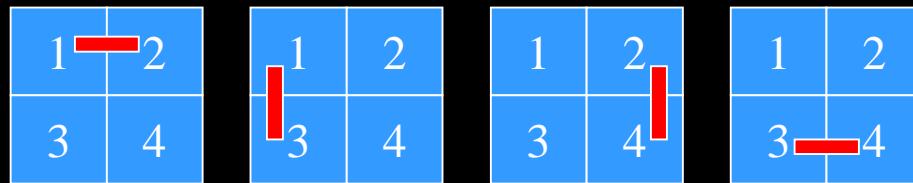


- *Unique* arrangement should be counted!



Multiplicity of Length Distribution

- $N[1]=2$
- $M[1]=4$



- $4 \times 3 \{M[1] \times (M[1]-1)\}$ ways of arranging the 2 interconnects

$$\Omega_L = \prod_{I=0}^{N[L]-1} (M[L] - I)$$

- Multiplicity of interconnects of length L

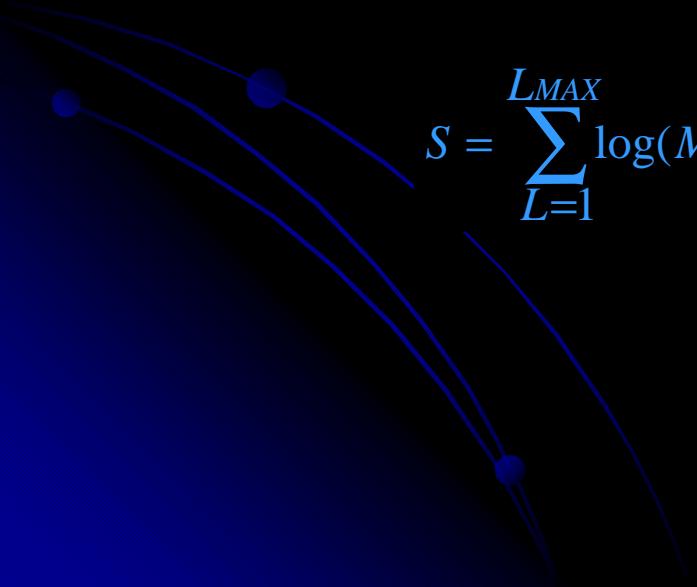
$$\Omega_L = \frac{M[L]!}{(M[L] - N[L])!}$$

Multiplicity Calculation

- Multiplicity of interconnect length distribution

$$\Omega = \prod_{L=1}^{2\sqrt{N}-2} \frac{M[L]!}{(M[L]-N[L])!}$$

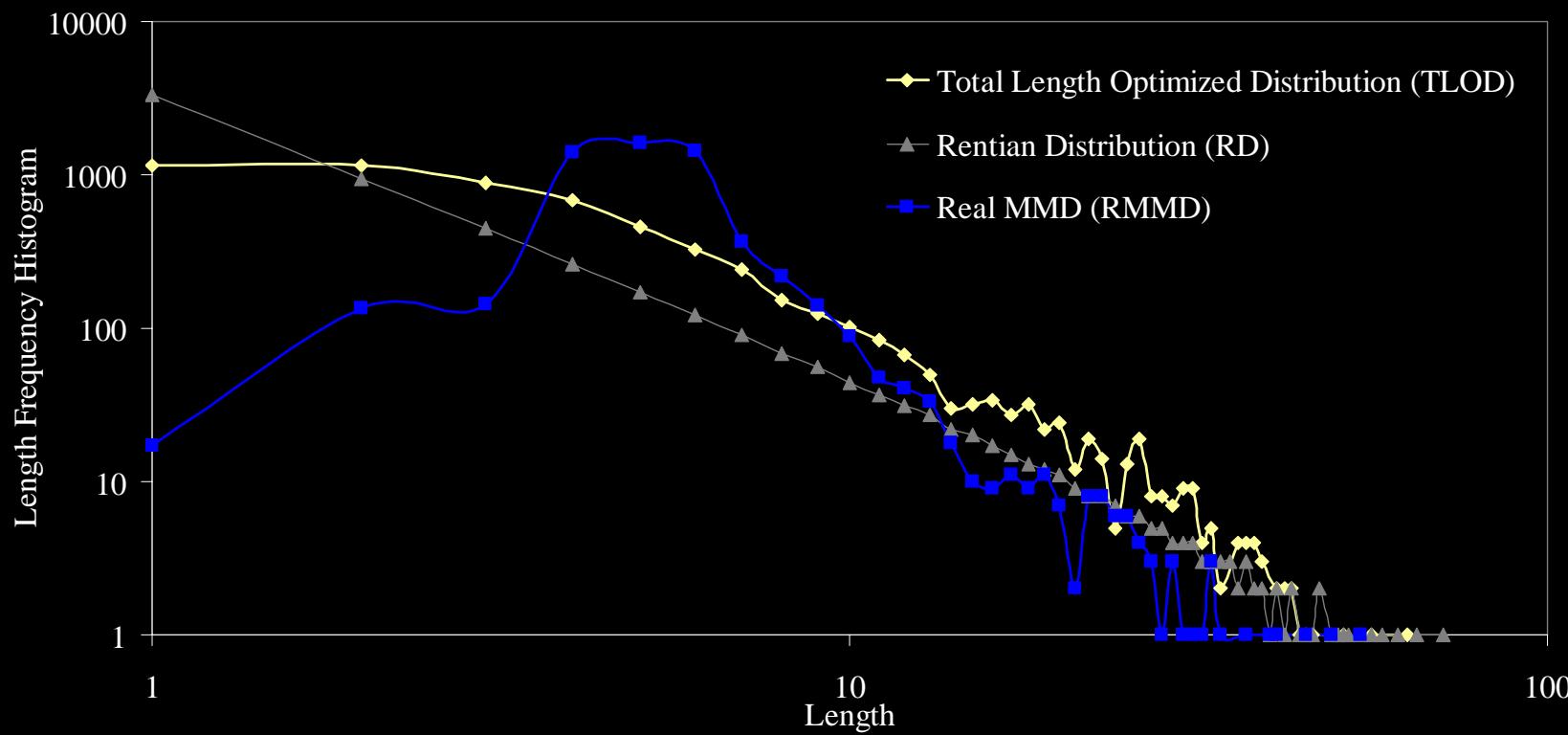
- Entropy


$$S = \sum_{L=1}^{L_{MAX}} \log(M[L]!) - \log((M[L]-N[L])!)$$

Length Distribution

C7552 Benchmark Circuit: 3512 Gates; 5836 Interconnects

Multiplicity of RD= 10^{20062} < Multiplicity of TLOD= 10^{21858} <
Multiplicity of RMMD= 10^{23084}



Outline

- Multiplicity
- *Theoretical MMD*
- Real MMD
- Impact on Global Interconnects
- Conclusion

MMD Problem Definition

- Find the values of $N(L)$ such that S

$$S = \sum_{L=1}^{L_{MAX}} \log(M[L]!) - \log((M[L] - N[L])!)$$

is maximized under the following constraints

$$N_{Edges} = \sum_{L=1}^{L_{MAX}} N[L] \quad L_{Total} = \sum_{L=1}^{L_{MAX}} L * N[L]$$

MMD Derivation

$$f_1 = \sum_{L=1}^{L_{MAX}} N[L] - N_{Edges}$$

$$f_2 = \sum_{L=1}^{L_{MAX}} L * N[L] - L_{Total}$$

$$\frac{\partial S}{\partial N[L]} + \alpha \frac{\partial f_1}{\partial N[L]} + \beta \frac{\partial f_2}{\partial N[L]} = 0$$

$$\log(K!) = K \log(K) - K$$

$$\frac{\partial \log(M[L] - N[L])!}{\partial N[L]} = -\log(M[L] - N[L]) \quad (5)$$

$$(1) \quad \frac{\partial \log(M[L] - N[L])!}{\partial N[L]} + \alpha + \beta L = 0 \quad (6)$$

(2)

$$-\log(M[L] - N[L]) + \alpha + \beta L = 0 \quad (7)$$

(3)

$$N[L] = M[L] - e^{\alpha + \beta L} \quad (8)$$

(4)

$$N[L] = M[L] - e^{\alpha} e^{\beta L} \quad (9)$$

$$a = e^{\alpha} \quad b = e^{\beta}$$

MMD Expression

$$N[L] = M[L] - a(b)^L$$

$$1 \leq L < \sqrt{N} :$$

$$M[L] = \frac{L^3}{3} - 2L^2\sqrt{N} + \frac{1}{3}L(6N-1)$$

$$\sqrt{N} \leq L < 2\sqrt{N} - 2 :$$

$$M[L] = -\frac{L^3}{3} + 2L^2\sqrt{N} - \frac{1}{3}L(12N-1) + \frac{2}{3}\sqrt{N}(4N-1)$$

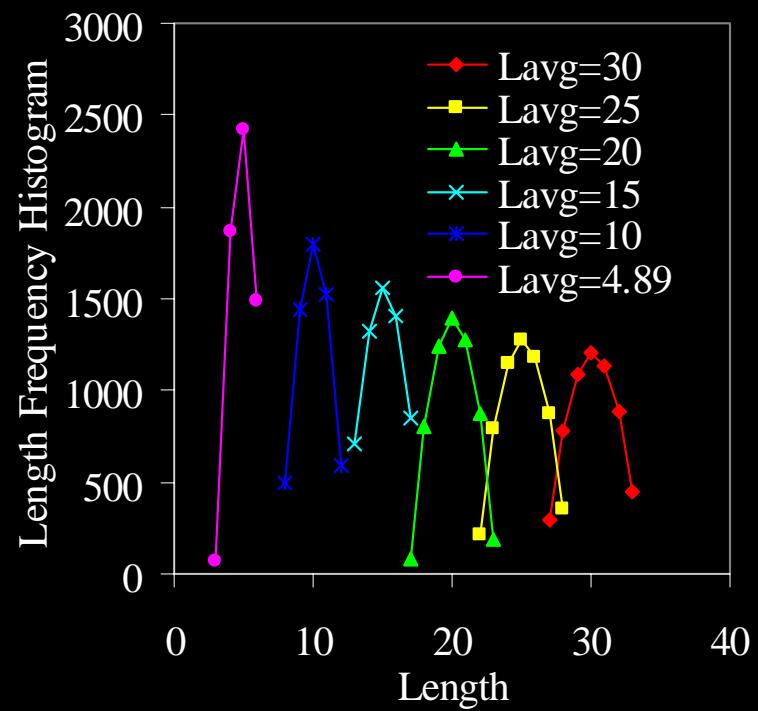
MMD Calculation

$$N[L] = \text{Max}(M[L] - a(b)^L, 0)$$

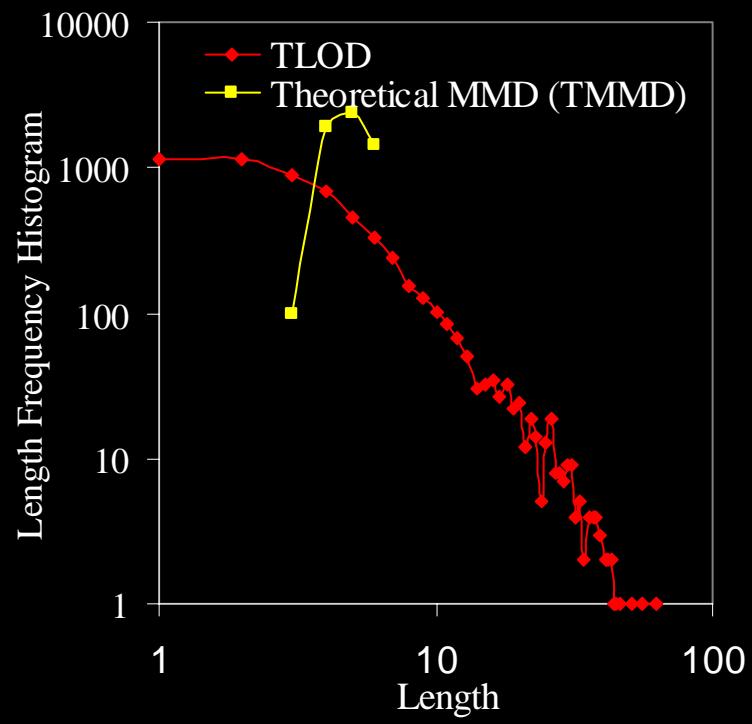
$$N_{Edges} = \sum_{L=1}^{L_{MAX}} \text{Max}(M[L] - a(b)^L, 0)$$

$$L_{Total} = \sum_{L=1}^{L_{MAX}} L * \text{Max}(M[L] - a(b)^L, 0)$$

MMD Calculation



MMD evolution for c7552 circuit with decreasing average length



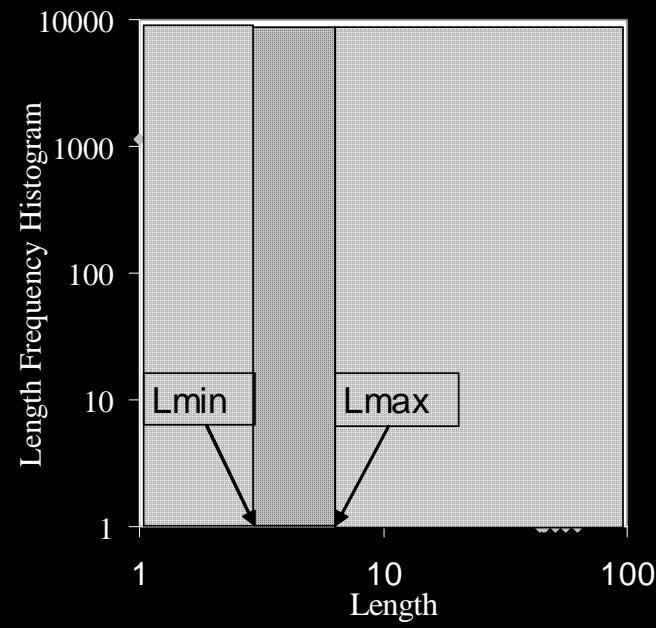
TLOD and MMD for c7552 benchmark circuit with average length of 4.89

Outline

- Multiplicity
- Theoretical MMD
- *Real MMD*
- Impact on Global Interconnects
- Conclusion

Real MMD

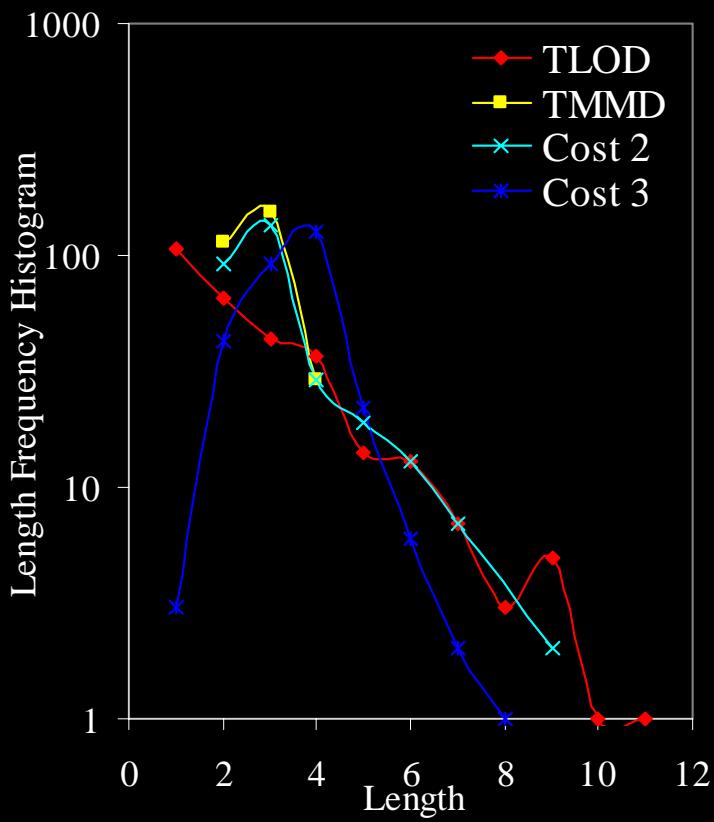
- Distribution Driven Placement



$$Cost = \sum W * |Nact[L] - Nreq[L]|$$

W values	Lact < Lmin	Lmin <= Lact <= Lmax	Lmax < Lact
<i>Cost1</i>	Lmin- Lact	Lact	Lact- Lmax
<i>Cost2</i>	Lmin- Lact	1	Lact- Lmax
<i>Cost3</i>	Lmin- Lact	0	Lact- Lmax
<i>Cost4</i>	Lact	Lact	Lact

Distribution Driven Placement



TLOD, Theoretical MMD, MMD-Distribution Matched (Real MMD) using cost function 2 and cost function 3

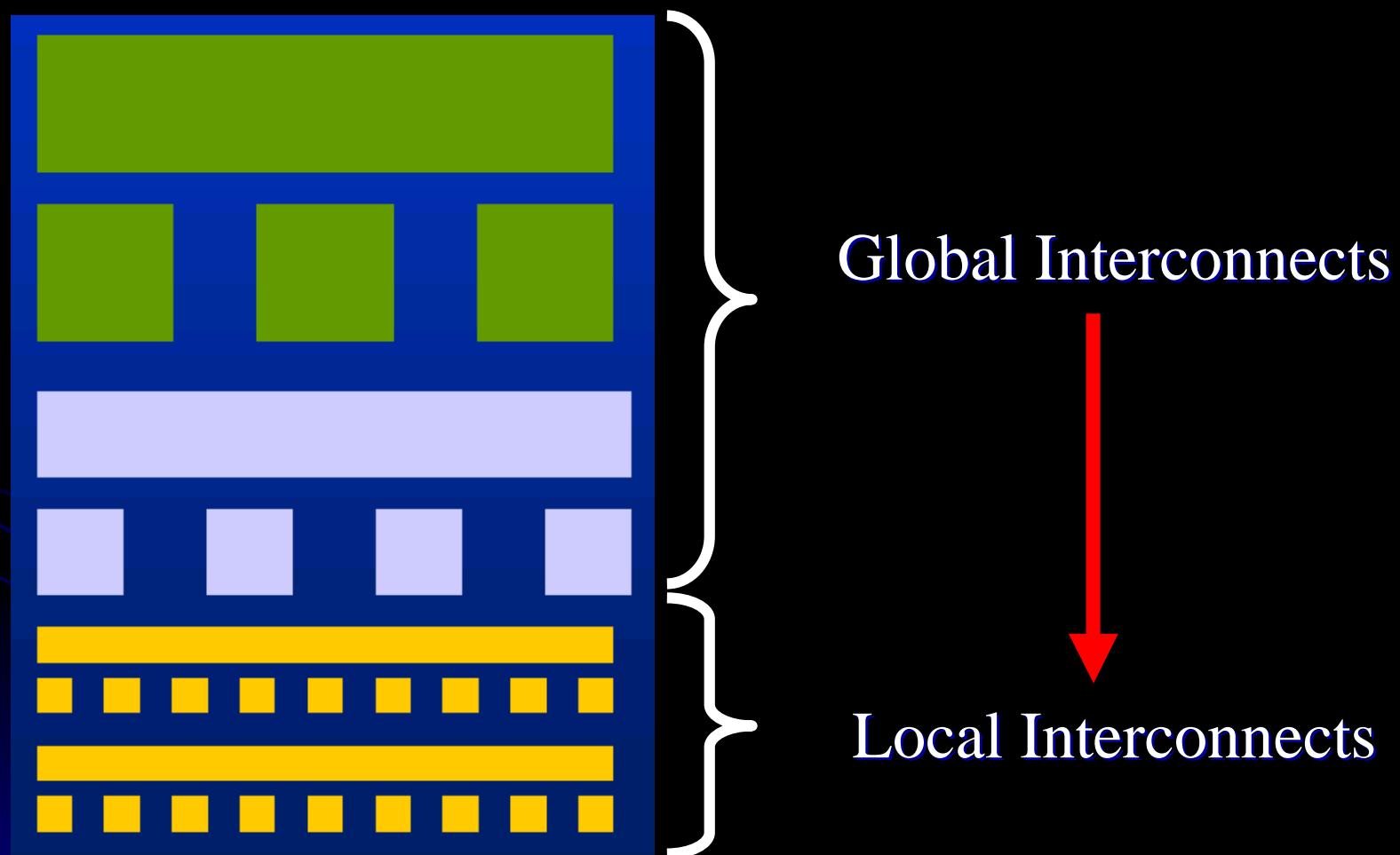
Circuit Name: C499	Cost1	Cost2	Cost3	Cost4
Cumulative % error	50.88	31.94	440.1	36.84
% Increase in total length	27.65	17.43	29.64	29.51

W values	Lact < Lmin	Lmin <= Lact <= Lmax	Lmax < Lact
<i>Cost1</i>	Lmin-Lact	Lact	Lact-Lmax
<i>Cost2</i>	Lmin-Lact	1	Lact-Lmax
<i>Cost3</i>	Lmin-Lact	0	Lact-Lmax
<i>Cost4</i>	Lact	Lact	Lact

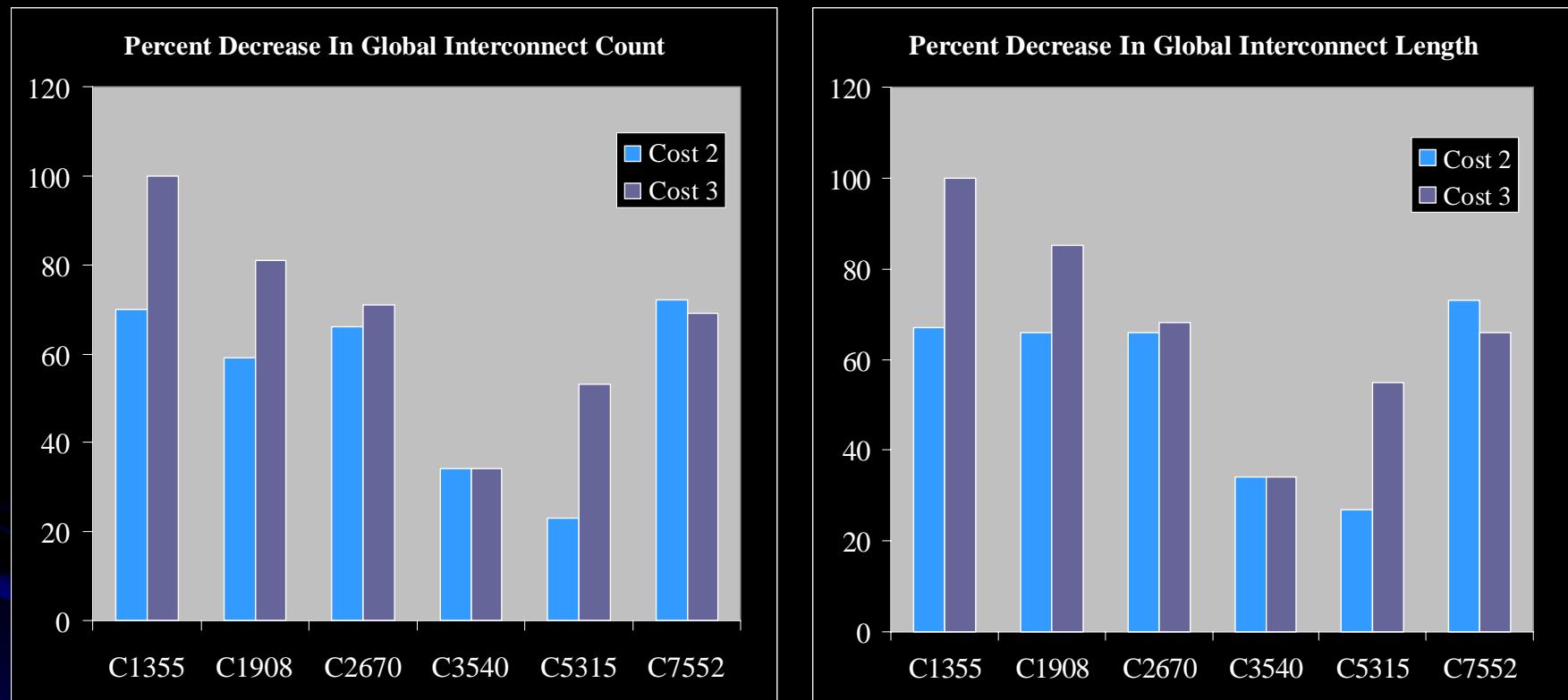
Outline

- Multiplicity
- Theoretical MMD
- Real MMD
- *Impact on Global Interconnects*
- Conclusion

Multilevel Interconnect Architecture

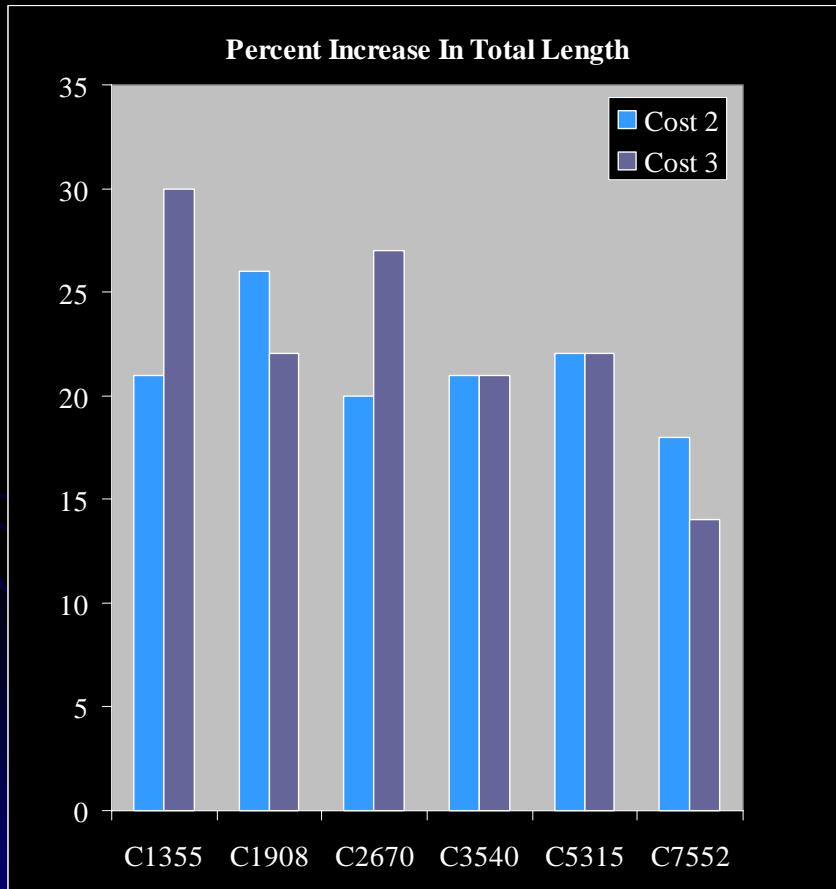


Global Interconnect



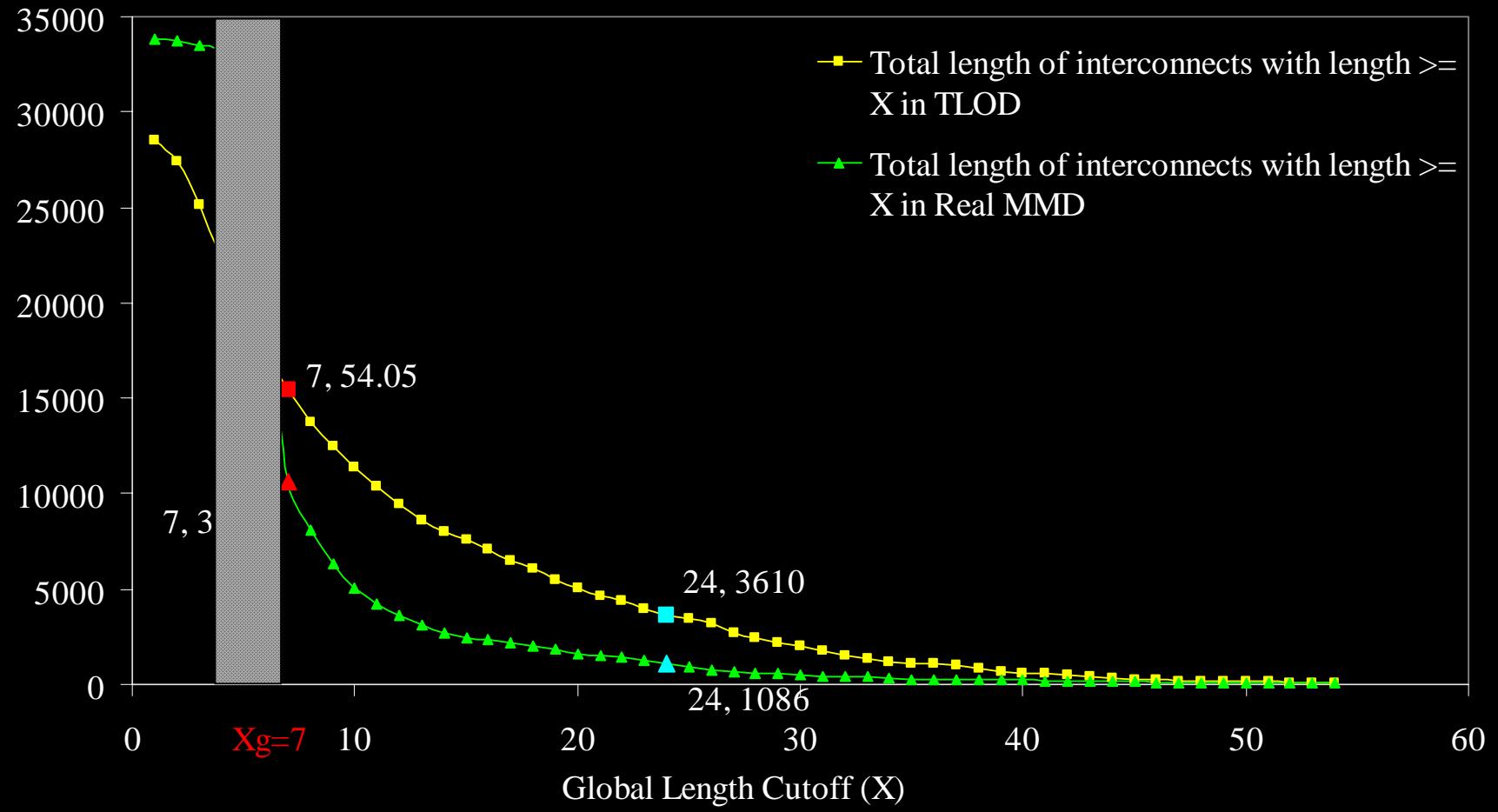
- Global Interconnect Cutoff = $0.2 \times L_{MAX}$
- Global Interconnect Count - average improvement: 54% (Cost 2) vs 68% (Cost 3)
- Global Interconnect Length - average improvement: 55% (Cost 2) vs 68% (Cost 3)

Total Interconnect Length



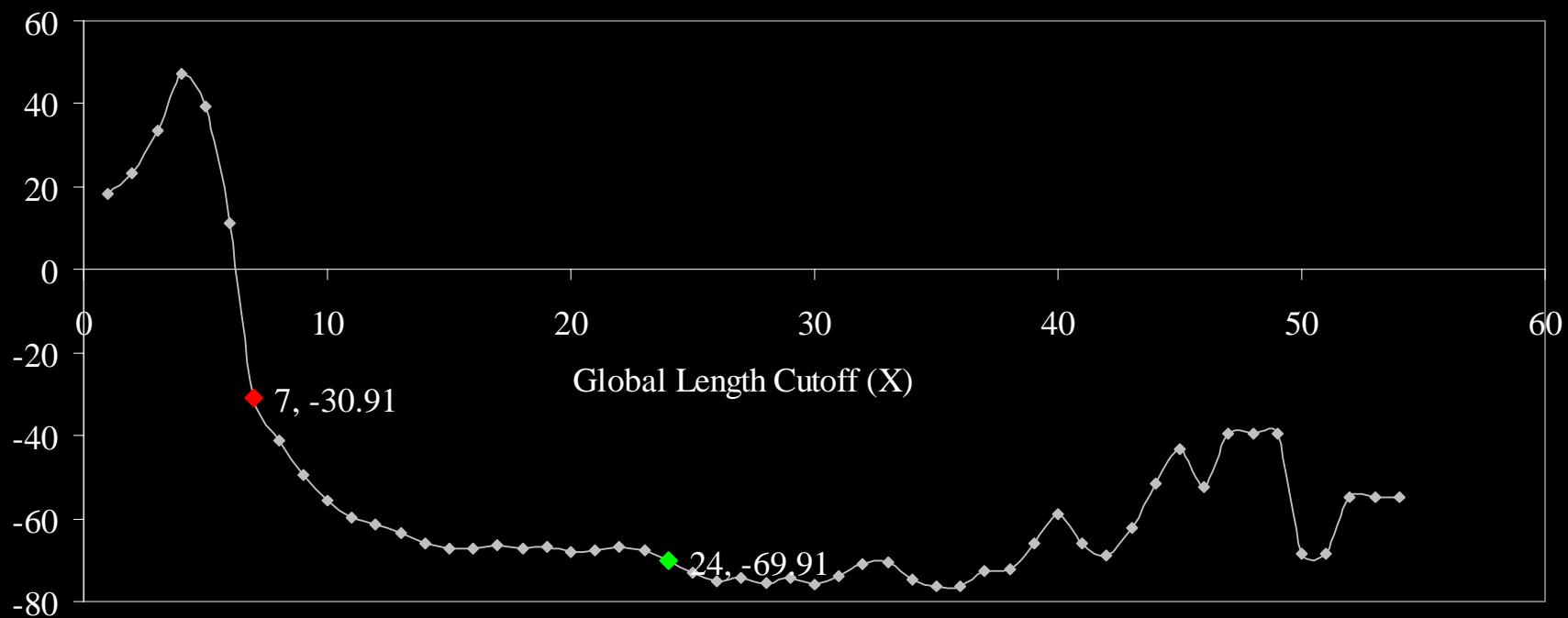
- Average increase in total length: 21% (cost 2) vs. 23% (cost 3)
- Interconnects with what length cause an increase in total length?
- What is the **least length** that we could use as **global interconnect cutoff** and see an improvement in global interconnect?

Global Interconnect Quality



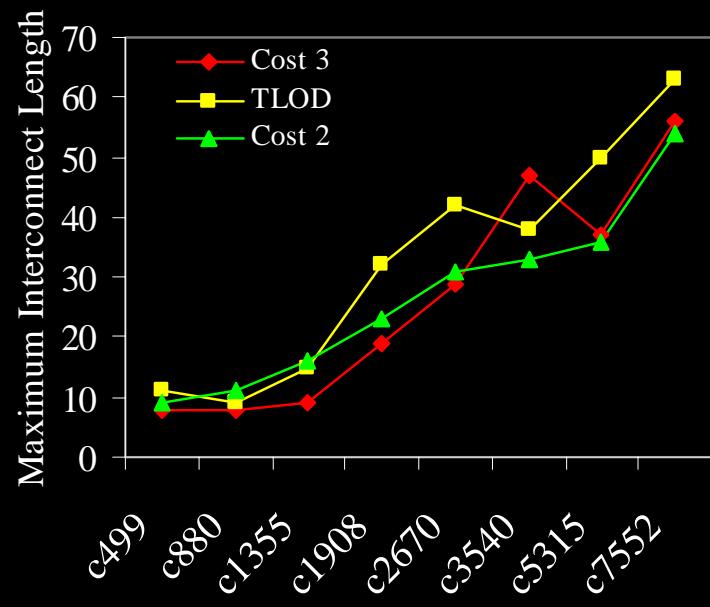
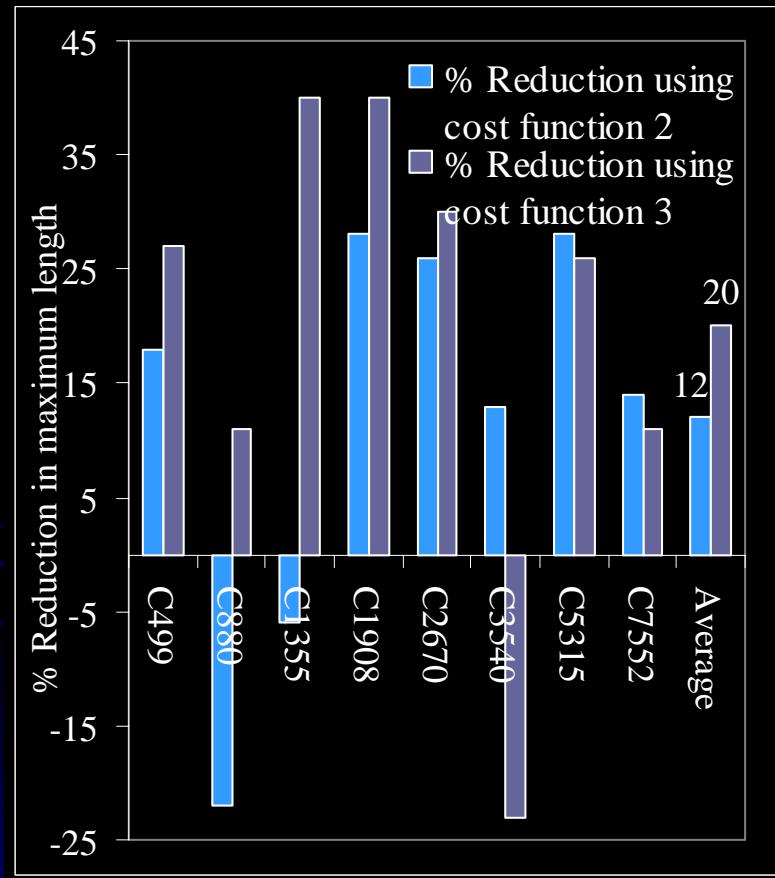
Global Interconnects

% Increase in total length of interconnects with length $\geq X$



Global Interconnect Quality

Maximum Length



Maximum interconnect length resulting from cost function 2, cost function 3 and TLOD for various circuits.

Outline

- Multiplicity
- Theoretical MMD
- Real MMD
- Impact on Global Interconnects
- *Conclusion*

Conclusion

- New interconnect length distribution
- Reduction in
 - Number of long interconnects (55%)
 - Total length of long interconnects (55%)
 - Maximum length of long interconnects (12%)
- Increase in total interconnect length due to local interconnects
- Insight into Distribution driven Physical Design

Questions

